

10797723_CLS.txt

Most Frequently Occurring Classifications of Patents Returned
From A Search of 10797723 on January 26, 2005

Original Classifications

4	250/251
3	204/298.04
3	250/423R
3	250/427
3	313/359.1
2	60/202
2	204/192.11
2	250/492.21
2	315/111.21
2	315/111.81
2	315/111.91

Cross-Reference Classifications

8	250/423R
8	315/111.81
6	313/231.31
6	315/111.41
5	315/111.31
4	204/298.16
4	313/359.1
4	313/362.1
4	313/363.1
3	204/298.19
3	250/398
3	315/111.21
3	376/130
3	428/408
3	428/694TC
2	204/192.11
2	204/298.36
2	250/251
2	250/305
2	250/397
2	250/492.2
2	250/492.21
2	313/231.41
2	313/360.1
2	313/361.1
2	315/111.61
2	315/111.91
2	376/147
2	427/527
2	427/580
2	428/336
2	976/DIG 437

Combined Classifications

11	250/423R
10	315/111.81
7	313/359.1
6	250/251
6	313/231.31
6	315/111.41
5	313/363.1
5	315/111.21
5	315/111.31
4	204/192.11
4	204/298.04

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4 204/298.16
4 250/427
4 250/492.21
4 313/362.1
4 315/111.91
4 376/130
4 428/408
3 60/202
3 204/298.19
3 250/398
3 313/360.1
3 427/580
3 428/336
3 428/694TC
2 118/723I
2 156/345.39
2 204/298.36
2 250/305
2 250/397
2 250/492.2
2 313/231.41
2 313/361.1
2 315/111.61
2 376/147
2 427/523
2 427/527
2 976/DIG 437

10797723_CLSTITLES.txt
Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 10797723 on January 26, 2005

- 11 250/423R (3 OR, 8 XR)
Class 250 : RADIANT ENERGY
250/423R ION GENERATION
- 10 315/111.81 (2 OR, 8 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.81 .Electron or ion source
- 7 313/359.1 (3 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
- 6 250/251 (4 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/251 ELECTRICALLY NEUTRAL MOLECULAR OR ATOMIC BEAM
DEVICES AND METHODS
- 6 313/231.31 (0 OR, 6 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS

313/231.31 .Plasma
- 6 315/111.41 (0 OR, 6 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.41 ..With magnetic field
- 5 313/363.1 (1 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/363.1 .Extraction or target electrode
- 5 315/111.21 (2 OR, 3 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
- 5 315/111.31 (0 OR, 5 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.31 ..With extraction electrode
- 4 204/192.11 (2 OR, 2 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/192.1 .Coating, forming or etching by sputtering
204/192.11 ..Ion beam sputter deposition

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- 4 204/298.04 (3 OR, 1 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/193 APPARATUS
204/298.01 .Coating, forming or etching by sputtering
204/298.02 ..Coating
204/298.04 ...Ion beam sputter deposition
- 4 204/298.16 (0 OR, 4 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/193 APPARATUS
204/298.01 .Coating, forming or etching by sputtering
204/298.02 ..Coating
204/298.16 ...Magnetically enhanced
- 4 250/427 (3 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/423R ION GENERATION
250/427 .Electron bombardment type
- 4 250/492.21 (2 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.21 ..Ion bombardment
- 4 313/362.1 (0 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/362.1 .Supplying ionizable material (e.g., gas or vapor)
- 4 315/111.91 (2 OR, 2 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.81 .Electron or ion source
315/111.91 ..Gas ionization type (e.g., ion pump or gauge source)
- 4 376/130 (1 OR, 3 XR)
Class 376 : INDUCED NUCLEAR REACTIONS: PROCESSES,
SYSTEMS, AND ELEMENTS
376/100 NUCLEAR FUSION
376/121 .Magnetic confinement of plasma
376/127 ..With injection of electrically charged or
accelerated particles
376/130 ...Neutral particle injection
- 4 428/408 (1 OR, 3 XR)
Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/408 SELF-SUSTAINING CARBON MASS OR LAYER WITH
IMPREGNANT OR OTHER LAYER
- 3 60/202 (2 OR, 1 XR)
Class 060 : POWER PLANTS
60/200.1 REACTION MOTOR (E.G., MOTIVE FLUID GENERATOR
AND REACTION NOZZLE, ETC.)
60/202 .Ion motor
- 3 204/298.19 (0 OR, 3 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/193 APPARATUS

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- 204/298.01 .Coating, forming or etching by sputtering
 - 204/298.02 ..Coating
 - 204/298.16 ...Magnetically enhanced
 - 204/298.17Flux passes through target surface
 - 204/298.19Planar magnetron
- 3 250/398 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSING
250/398 .With target means
- 3 313/360.1 (1 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/360.1 .Plural apertured electrodes
- 3 427/580 (1 OR, 2 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/580 .Electrical discharge (e.g., arcs, sparks,
etc.)
- 3 428/336 (1 OR, 2 XR)
Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/221 WEB OR SHEET CONTAINING STRUCTURALLY DEFINED
ELEMENT OR COMPONENT
428/332 .Physical dimension specified
428/334 ..Coating layer not in excess of 5 mils thick
or equivalent
428/335 ...Up to 3 mils
428/3361 mil or less
- 3 428/694TC (0 OR, 3 XR)
Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
428/688 .of inorganic material
428/689 ..Metal-compound-containing layer
428/692 ...Defined magnetic layer
428/694RDynamic recording medium
428/694TMetal thin film magnetic layer
428/694TPTopcoat, or protective overlayer
428/694TCCarbon
- 2 118/723I (1 OR, 1 XR)
Class 118 : COATING APPARATUS
118/715 GAS OR VAPOR DEPOSITION
118/722 .With treating means (e.g., jarring)
118/723R ..By creating electric field (e.g., gas
activation, plasma, etc.)
118/723I ...Radio frequency antenna or radio frequency
inductive coil discharge means
- 2 156/345.39 (1 OR, 1 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/345.1 DIFFERENTIAL FLUID ETCHING APPARATUS
156/345.39 .With means to generate and to direct a
reactive ion etchant beam at a workpiece
- 2 204/298.36 (0 OR, 2 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

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204/193 APPARATUS
204/298.01 .Coating, forming or etching by sputtering
204/298.31 ..Etching
204/298.36 ...Beam or directed flux etching (e.g., ion beam, etc.)

2 250/305 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/305 ELECTRON ENERGY ANALYSIS

2 250/397 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/397 .with detector

2 250/492.2 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices

2 313/231.41 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS

313/231.31 .Plasma
313/231.41 ..Arc discharge type

2 313/361.1 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/361.1 .Means for deflecting or focusing

2 315/111.61 (0 OR, 2 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.41 ..With magnetic field
315/111.61 ...Acceleration

2 376/147 (0 OR, 2 XR)
Class 376 : INDUCED NUCLEAR REACTIONS: PROCESSES,
SYSTEMS, AND ELEMENTS
376/100 NUCLEAR FUSION
376/146 .Including removal or use of impurities or
reaction products (e.g., energy)
376/147 ..Direct conversion of energy

2 427/523 (1 OR, 1 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/523 .Ion plating or implantation

2 427/527 (0 OR, 2 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/523 .Ion plating or implantation
427/527 ..Silicon present in substrate, plating, or
implanted layer

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2 976/DIG 437 (0 OR, 2 XR)
Class 976 : NUCLEAR TECHNOLOGY
976/DIG 427 ARRANGEMENTS FOR HANDLING RADIATION OR
PARTICLES (e.g., focusing, moderating [G21K-1/00] ***
(radiation filters DIG. 435)
976/DIG 437 .Using charge exchange devices (e.g., for
neutralizing or changing the sign of the electrical
charges
of beams) [G21K-1/14] *** (producing or accelerating
neutral particle beams H05H-3/00).